



IEUVI Resist TWG February 21, 2010

Preliminary Agenda

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| 1:00 PM - 1:15 PM | Welcome and Introduction |
| 1:15 PM - 2:30 PM | Discussion Topics I: <ul style="list-style-type: none">- LWR/LER reduction efforts<ul style="list-style-type: none">○ Can we combine Mask + Resist + post processing improvements to meet tight FCCD specs?○ Pattern specific geometries, 2D implications?○ Are we on track to meet 30 & 22nm LWR Specs? |
| 2:30 PM - 2:45 PM | Break |
| 2:45 PM - 4:00 PM | Discussion Topics II : <ul style="list-style-type: none">- Resist design to Improve RLS- Resist outgassing RGA / Witness plate<ul style="list-style-type: none">○ Is there list of Good Vs Bad molecules?- Is EUV maturing at appropriate pace? |
| 4:00 PM | Adjourn |